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Substitute for form 1449B/PTO		Complete if Known	
		Application Number	10/672,110
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)		Filing Date	September 26, 2003
		First Named Inventor	Max Christian Schuermann, et al.
		Art Unit	2884
		Examiner Name	Otilia Gabor
		Attorney Docket Number	500814.20073
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NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
OG		"Reflectometer for EUV Lithography Components", Research Disclosure, July 2001, page 1146	
OG		V. Paret, et al. "Characaterization of Optics and Masks for EUV Litography," Microelectronic Engineering 61-62 (2002), Pages 145-155	
OG		H. Kondo, et al. "Development of EUV Reflectometer Using a Laser-Plasma X-Ray Source," Page 34	
OG		E.M. Gullikson et al. "A Soft X-ray/EUV Reflectometer Based on a Laser Produced Plasma Source" Journal of X-ray Science and Tecnology 3 (1192), Pages 283-299	
OG		D.L. Windt et al. "Multilayer Facilities Required for Extreme-Ultraviolet Lithography", 8257b Journal of Vacuum Science & Technology B (1994), Pages 3826-3832	
OG		M. Cui et al. "Synchrotron Radiation Soft X-ray Reflectometers and its Phusic Results" Nuclear Instruments and Methods in Physic Research A (1995), Pages 151-154	
OG		G. Schriever et al. "Laser-Produced Lithium Plasma as a Narrow-Band Extended Ultraviolet Radiation Source for Photoelectron Spectroscopy", Applied Optics (1998), Pages 1423-1248	

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